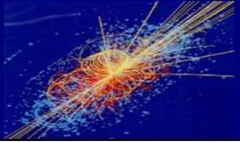

Front-End Electronics developments for the Microvertex detector of the PANDA Experiments at FAIR

D. Calvo[1], T. Kugathasan[1,2], P. De Remigis[1], G.Mazza[1],
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1 INFN, Sezione di Torino, Italy
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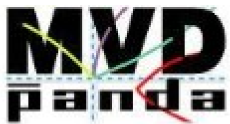
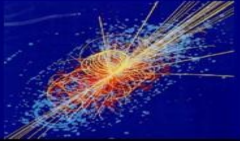
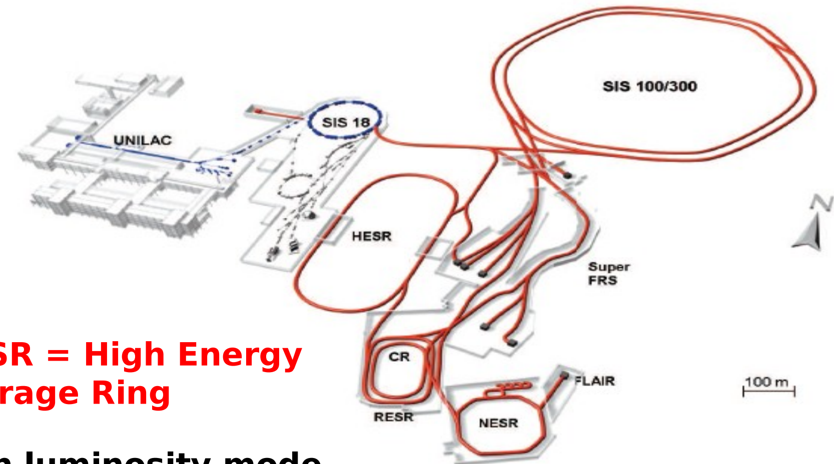


PANDA @ FAIR





HESR = High Energy Storage Ring

High luminosity mode

- **Luminosity = $2 \times 10^{32}\ cm^{-2}s^{-1}$**
- **$\delta p/p \sim 10^{-4}$ (stochastic cooling)**

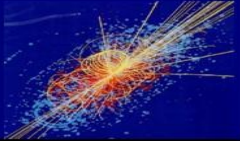
High resolution mode

- **$\delta p/p \sim 10^{-5}$ (el. cooling < 8 GeV/c)**
- **Luminosity = $10^{31}\ cm^{-2}s^{-1}$**

- **FAIR: Facility for Antiproton and Ion Research.**
- **PANDA: Pbar ANnihilation at Darmstadt. Multipurpose experiment:**
  - **charmonium spectroscopy**
  - **glueballs and hybrids**
  - **hadrons in nuclear matter**
  - **open charm production**
  - **γ-ray spectroscopy of hypernuclei**

TRIGGERLESS READOUT

The PANDA apparatus



Target Spectrometer

Forward Spectrometer

Solenoid

Target

Muon ID

Dipole

Drift Chambers

DIRC

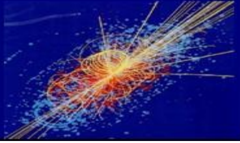
Vertex

Straws/TPC

Elektromag. Calorimeter

Cherenkov

Hadron Calorimeter



The Micro-Vertex Detector

r / mm
135
95
55
25
Target
4
3
2
1
Beam
r_{max} = 150 mm
1 2 3 4 5 6
-230
-170
20 40 70 100 160 230
z / mm

6 disk layers

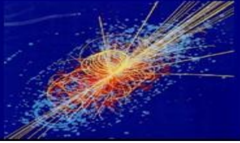
4 barrel layers

Silicon detectors:

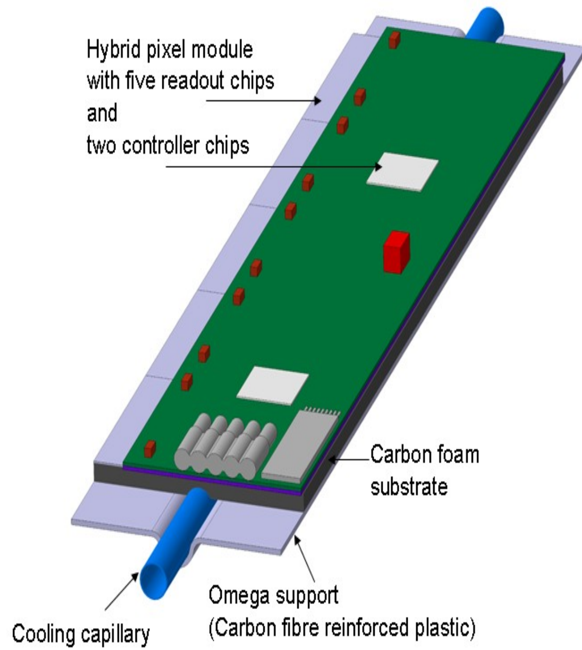
- ✓ Hybrid pixel detectors
- ✓ Double-sided microstrip detectors

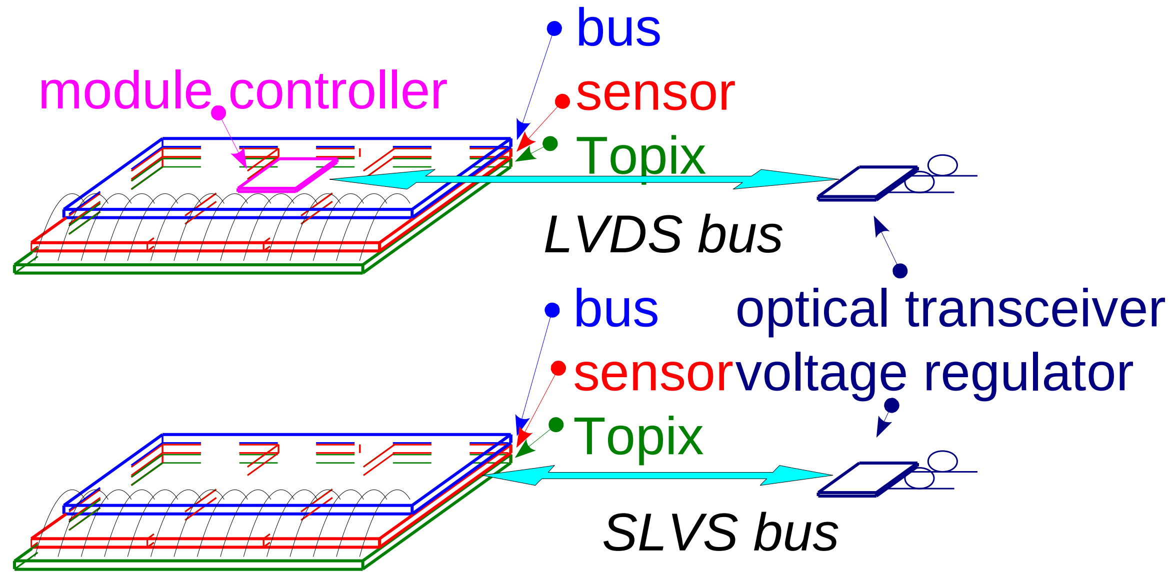
The Micro-Vertex Detector

- 10 million pixel channels on 176 modules
- 200,000 strip channels on 254 modules



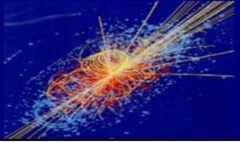
The hybrid pixel detector





- Baseline solution based on well-proven technology (hybrid pixel with bump bonding)
- Custom development only where strictly needed (e.g. front-end chip)

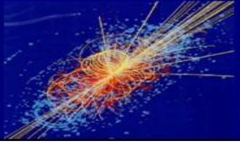
Specs for the pixel detector



- **Pixel cell specs:**
  - **Pixel size: 100 μm x 100 μm.**
  - **Noise level: < 200 e- rms.**
  - **Linear dynamic range: up to 50 fC.**
  - **Power consumption: < 20 μW.**
  - **Selectable input signal polarity.**
  - **Leakage insensitive up to 50 nA.**

- **ASIC specs:**
  - **Self triggering**
  - **Clock 160 MHz**
  - **Active area: O(1 cm^2)**
  - **Data rate: O(0.8 Gbit/sec.)**
  - **Radiation tolerance: LHC grade.**
  - **Simultaneous time stamping and charge measurement.**

- **No existing chip could match simultaneously all the PANDA requirements.**
- **Custom solution under investigation.**
- **Technology: CMOS 0.13 μm.**

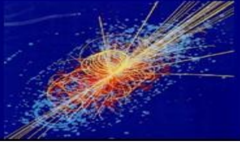


ASIC architecture

Pixel-ID
LE-REG
TE-REG
CFG-REG
Hit logic
Dummy hit generator
12-bit Gray code counter
dummy pixel detect
column control
Write
Empty
Full
Almost full
DP present
Read
16 storage cells
DP clear
EoC event generator
EoC create
Readout control
Data serializer
Busy

- Time-stamp (Gray encoded) distributed to the pixels and stored into local registers (à la ATLAS).
- Sixteen cells deep-FIFO at the end of each column.
- 800 Mbit/sec per cm^2 max data rate.
- Power supply: 1.2 V.

Pixel cell architecture



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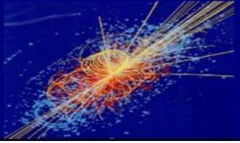
Front-end amplifier



Vdd

Ibias

select_polb

bias_sfP

VcasP

VcasN

Vout

Input

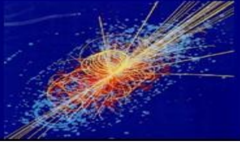
bias_sfN

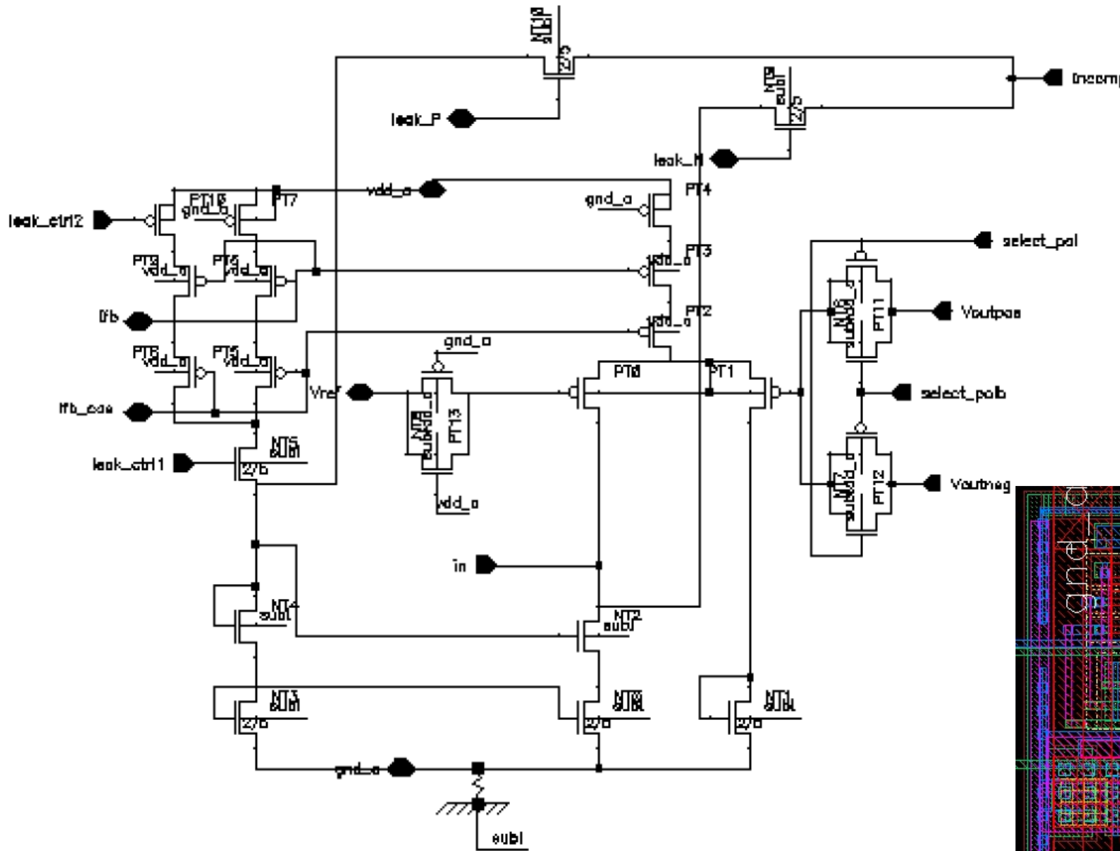
DC level fixed by transistor bias (0.3 V)

Output DC level regulated by the baseline restorer. (0.3 V for n-type sensor, 0.8 V for p-type)

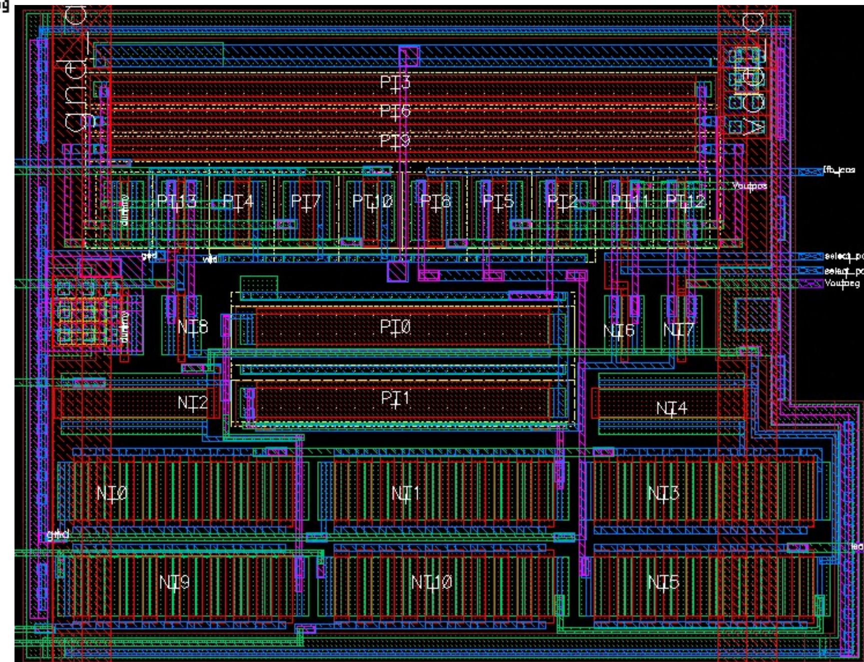
- **Direct cascode with NMOS input transistor and split current source**
- **Triple well NFET input and cascode.**
- **Two selectable PMOS or NMOS output buffers.**
- **Current: 2μA in the input device, 1 μA in the source follower.**

Feed-back current switch



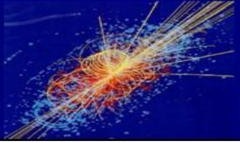


- **Differential current switch.**
- **At the equilibrium provides an equivalent 8MΩ feed-back resistor.**



- **Issue: low-value of feed-back current (2.5nA to 10 nA) leads to long devices.**

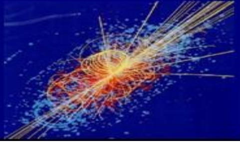
Leakage compensation



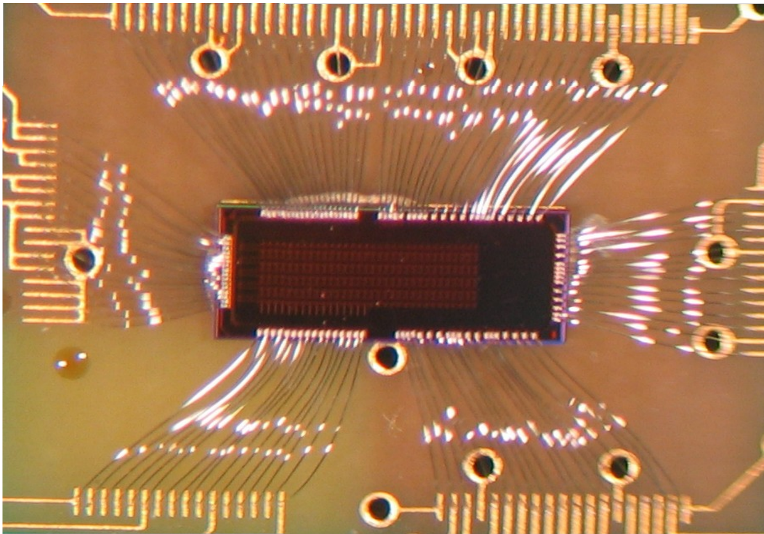
➢ **With large dynamic range ToT signals ca be very long (10-20 μs).**

➢ **Leakage compensation must be very narrowband, otherwise a non-linearity will result**

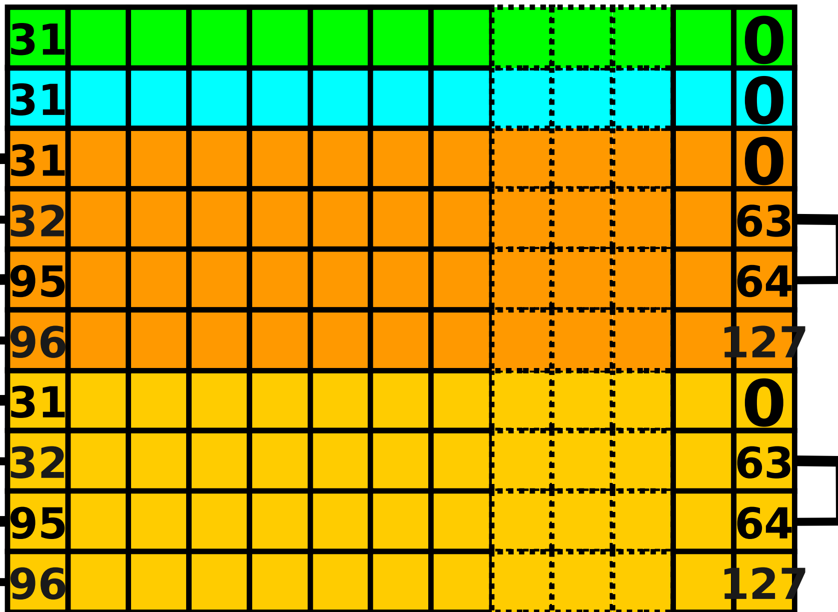
➢ **Need to implement compact filtering resistors with very high value.**



Chip prototype

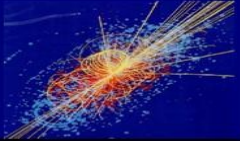


- Test chip produced in a MPW.
- Size: 5 mm x 2 mm.
- Column length: 12.8 mm.
- Column folding => full bus length.



- Full pixel cell (analog and digital parts).
- Simplified end-of-column logic.
- Two folded columns with 128 pixels.
- Two short column with 32 pixels.
- Sixteen pixels with wire bonding pad.

Reconstructed pulse shape



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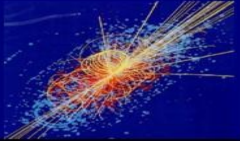
Linearity



ToT [us]

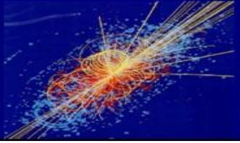
18
16
14
12
10
8
6
4
2
0

0 20 40 60 80 100 120

Input charge [fC]

Pixel 16
Pixel 21

Across chip ToT variation



ΔToT/ToT (%)

15

10

5

4n 6n 8n 10n 12n 14n

Discharge current (A)

Measure: threshold dispersion

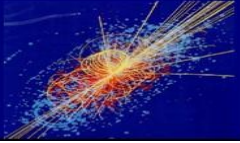
Topix2
Before correction
After correction

300
250
200
150
100
50
0

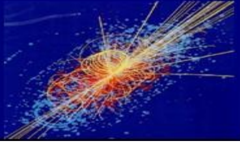
0.78 0.79 0.80 0.81 0.82

Baseline (V)

Measure: calibration with Am source



Standard p-type sensor 300 μm thick:



Epitaxial silicon sensor (1)

Lightly doped epitaxial layer

Highly doped Cz substrate:
r = 0.01 – 0.02 Ω cm

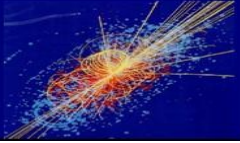
- **Several studies indicate that sensor build on epi wafer have good radiation tolerance.**
- **Interest for PANDA: radiation tolerance adequate with standard p-type design.**

Wafers supplied by ITME and processed by FBK-IRST in Trento
Project partially funded with through the ULISI-FP7 program

- **Substrate properties:**
  - **Diameter: 100 ± 0.5 mm.**
  - **Doping type: n/Sb.**
  - **Thickness 525 ± 25 μm.**
  - **Resistivity: 0.01 – 0.02 Ω cm.**

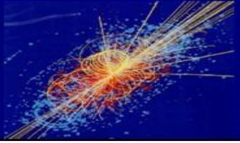
- **Epi layer properties:**
  - **Doping: time n/P.**
  - **Thickness 50/75/100 μm.**
  - **Variation: <4%/8%/8%**
  - **Resistivity: 2500 – 5000 Ω cm.**

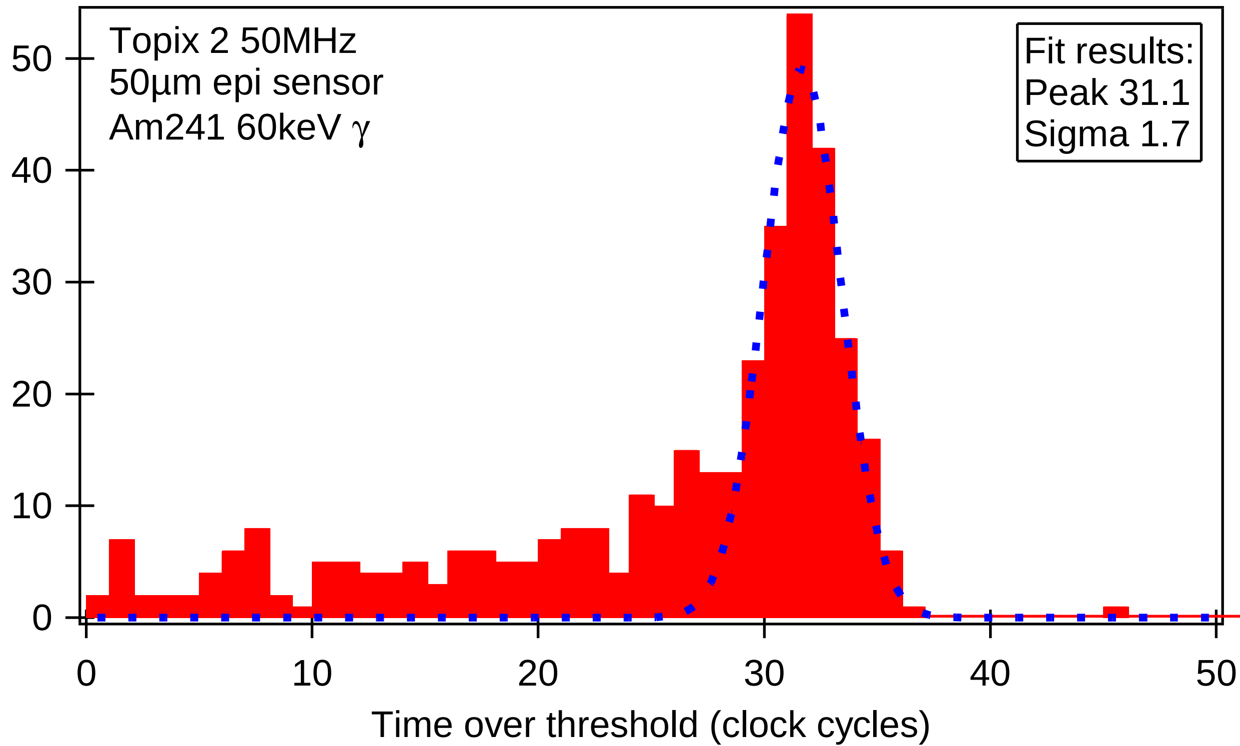
Epitaxial silicon sensor (2)

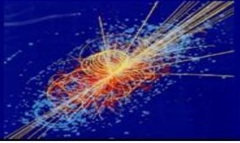


- **Low cost R&D reusing existing electronics and sensor design:**
  - **Electronics: ALICE front-end chip provided by CERN**
  - **Sensor: masks developed by INFN-Ferrara for NA62 project.**
- **Three types of epi assemblies:**
  - **3 with 150 μm total thickness (100 μm epi)**
  - **7 with 120 μm total thickness (75 μm epi)**
  - **1 with 100 μm total thickness (50 μm epi)**
  - **Spare sensors to be wire-bonded to the prototype**

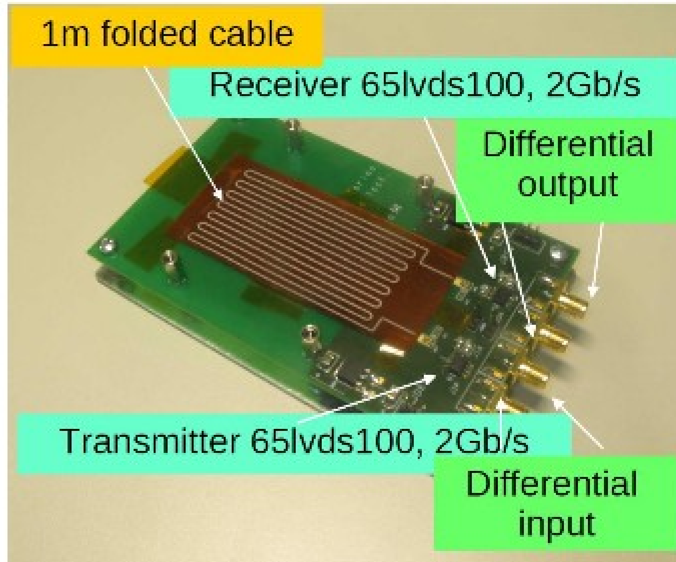
First spectra with an epi-sensor

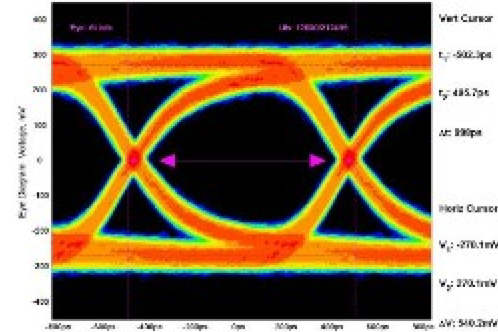






Data transmission cables





Techfab: 7µm Al on 50 µm Kapton
CERN: 15 µm Al on 70 µm Kapton

- 2-3 300 Gbit/sec link per front-end
- Al cable with 2Gbit/sec under study
- Transmission from the MVD to the counting room via the GBT chip set (under development at CERN).

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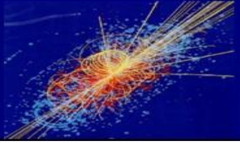
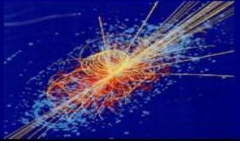
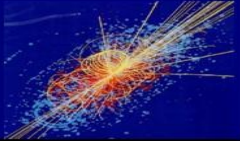
Next steps



- Sumbit a new version on the front-end chip (scheduled for Nov. 2010)
  - Minor modifications in the analogue part
  - Opening for bump bonding
  - Migration to the baseline flavor of the process (thick upper metals for power distribution).
  - Full end of column logic
- Bump bonding with epitaxial silicon sensors
- 2011 devoted to detail testing
- Start the preparation of the engineering run in 2012.



SPARE SLIDES

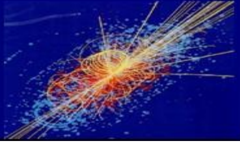


Dynamic range

Cfeed

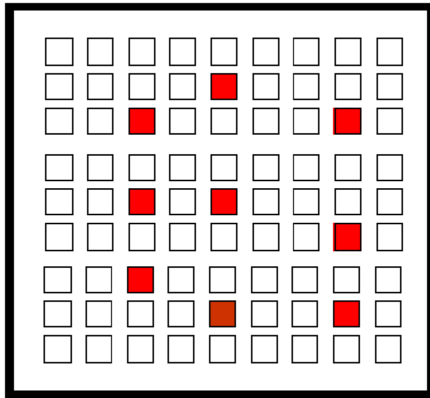
Cin

- Linear mode (core amplifier not saturated): the signal charge is integrated on the feed-back capacitor Cfeed and removed by a constant current: 0.7 V/24 fF=16.8 fC.
- Saturated mode (core amplifier gain drops): the signal is integrated on the input capacitor and removed by a constant current
- Qmax=0.3V x 200 fF=60fC (n-type sensors) or 0.7V x 200 fF=140fC (p-type sensors).



Saturation and cross-talk (1)

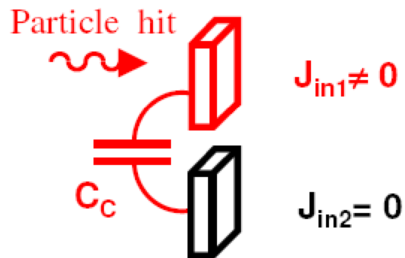
Pixel Matrix

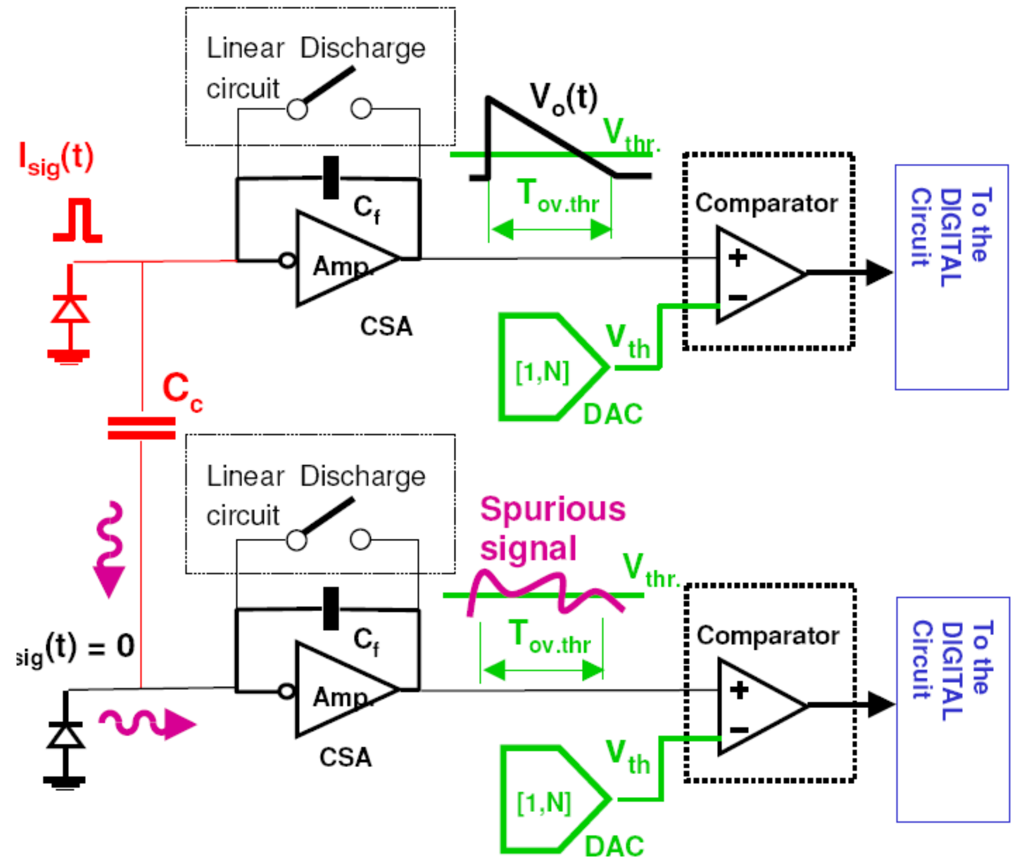


hit event

no hit event

Adjacent Coupled Detectors





Saturation and cross-talk (2)